

ECH 4905/ECH 6937 Semiconductor Device Fabrication and Material Characterization

1. Instructor - Fan Ren
 - a. Office location: CHE 427
 - b. Telephone: 352-392-4727
 - c. E-mail address: ren@che.ufl.edu
 - d. Location: Zoom meeting (will be posted on Canvas)
2. Office hours: make appointments with email
3. Catalog Description – (3 credits) The overall goal is to provide students with knowledge in semiconductor material characterization and device fabrication techniques.
4. Pre-requisites and Co-requisites: None
5. Course Objectives -
 - a. Students will gain knowledge in semiconductor based processes, units, and corresponding equipment.
 - b. Students will gain knowledge in to design and fabricate the devices.
 - c. Students will be able to use the scientific method and problem solving strategies, as well as statistical methods, to design and carry out experiments in order to solve engineering problems.
 - d. Students will demonstrate familiarity and experience with the capabilities and limitations of semiconductor process equipment.
 - e. Students will understand and practice safe laboratory and chemicals-handling principles.
 - f. Students will be able to integrate topics from various semiconductor processing steps to solve realistic problems in the areas of material and device characterization.
 - g. Students will exhibit critical and creative thinking skills for analysis and evaluation of problems and cause-effect relationships.
 - h. Students will be able to obtain and evaluate appropriate informational/data from databases, handbooks, correlations, experiments, literature, etc.
 - i. Students will be able to rationalize units, make order of magnitude estimates, assess reasonableness of solutions, and select appropriate levels of solution sophistication.
 - j. Students will demonstrate effective reading of technical material.
 - k. Students will demonstrate effective interpretation of graphical data.
 - l. Students will practice good teamwork principles.
 - m. Students will gain general concepts of estimating mass-transfer coefficients and use them to determine mass-transfer rates across phase boundaries during oxide growth.
 - n. Students will demonstrate knowledge of photolithographic chemistry.

- o. Students will understand fundamentals of vacuum deposition including thermal evaporation and sputtering deposition systems.

6. Materials and Supply fees: N/A

7. Required Textbook and Software

No textbook required

Software Required – SRIM and Layout Editor

- (a) Download the SRIM-2013 (Professional) software from <http://www.srim.org/SRIM/SRIMLEGL.htm>. Download the file and follow the procedures indicated on the website but when you rename the file “SRIM-2013-Pro.e” use the name ZIP.exe to avoid confusions later. **Please make sure your windows language and version are English.**

After extracting the file open the “SRIM-Setup” folder. Right click on the “_SRIM-Setup (Right-Click).bat” and select “Run as administrator”. Follow indicated procedures.

Go back to the uncompressed folder and open the “SRIM.exe” file (this is the software link). Be sure you can access the Stopping/Range table and also the TRIM Calculation window and they appear complete on the screen.

- (b) Download “layout editor” from the link below from <https://layouteditor.org/> and install it.

8. Recommended Reading -

Stephen A. Campbell, The Science and Engineering of Microelectronic Fabrication, Second Edition ed.: Oxford University Press, 2001.

Dieter K. Schroder, Semiconductor material and device characterization, Third Edition ed.: John Wiley & Sons, Inc., 2006.

G.S. May and S.M. Sze, Fundamentals of semiconductor fabrication.: Wiley, 2004.

9. Course Schedule

<i>Wk</i>	<i>Date</i>	<i>Topic</i>	<i>HW</i>
1	1/11	Semiconductor I	
	1/13	Semiconductor II	
	1/15	Field Effect Transistor and Bipolar Transistor	HW Semiconductor
2	1/18	Four point measurement, transmission line method, Schottky diode characterization, Hall Measurement	

	1/20	Oxidation I	HW Measurement
	1/22	Oxidation II	
3	1/25	Ion Implantation	HW Oxidation
	1/27	Ion Implantation	
	1/29	SRIM I	
4	2/1	Exam I (Semiconductor/Oxidation)	
	2/3	SRIM II	
	2/5	Chemical Vapor Deposition (CVD) I	HW Implantation
5	2/8	Molecular Beam Epitaxy	
	2/10	Metal Organic CVD	
	2/12	Plasma Enhanced Vapor Deposition (OECVD)	
6	2/15	Diffusion in Solid I	HW CVD
	2/17	Diffusion II	
	2/19	Evaporation	HW Diffusion
7	2/22	Sputter	
	2/24	Vacuum Gauge	HW Metal deposition
	2/26	Vacuum Pump	
8	3/1	Exam II (Ion Implantation, CVD, Metal Deposition and Diffusion)	
	3/3	Photo Resist I	HW Vacuum Pump
	3/5	Photo Resist II	
9	3/8	Photolithography	
	3/10	Mask Design I	HW Photolithography
	3/12	Mask Design II	
10	3/15	Mask Design III	
	3/17	Wet and plasma etching I	HW Mask design
	3/19	Wet and plasma etching II	
11	3/22	Wet and plasma etching III	
	3/24	Surface Analysis (SEM)	HW Etching
	3/26	XPS/Auger	
12	3/29	Exam III (Photolithography, Vacuum Pump and Etching)	
	9/31	Auger/SIMS/RBS	
	4/2	Crystal I	HW Surface Analysis
13	4/5	Crystal II	
	4/7	x-ray	
	4/9	Defects	
14	4/12	Presentation	HW Crystal and x-ray
	4/14	Presentation	
	4/16	Presentation	
15	4/19	No Class	
	4/21	Exam 4 (Crystal/Surface Analysis)	

10. Grading – methods of evaluation (50% for exams (3 highest scores out of 4 exams), 40% for homework (one homework with the lowest score will be dropped), 10% for presentation)

Grading Scale

Percent	Grade	Grade Points
90.0 - 100.0	A	4.00
87.0 - 89.99	A-	3.67
84.0 - 86.99	B+	3.33
81.0 - 83.99	B	3.00
78.0 - 80.99	B-	2.67
75.0 - 79.99	C+	2.33
72.0 - 74.99	C	2.00
69.0 - 71.99	C-	1.67
66.0 - 68.99	D+	1.33
63.0 - 65.99	D	1.00
60.0 - 62.99	D-	0.67
0 - 59.99	E	0.00

More information on UF grading policy may be found at:

[UF Graduate Catalog](#)

[Grades and Grading Policies](#)

Students Requiring Accommodations

Students with disabilities who experience learning barriers and would like to request academic accommodations should connect with the [Disability Resource Center](#). It is important for students to share their accommodation letter with their instructor and discuss their access needs, as early as possible in the semester.

Course Evaluation

Students are expected to provide feedback on the quality of instruction in this course by completing [online evaluations](#). Evaluations are typically open during the last two or three weeks of the semester, but students will be given specific times when they are open. Summary results of these assessments are available to students on the [Gator Evals page](#).

University Honesty Policy

UF students are bound by The Honor Pledge which states, “We, the members of the University of Florida community, pledge to hold ourselves and our peers to the highest standards of honor and integrity by abiding by the Honor Code. On all work submitted for credit by students at the University of Florida, the following pledge is either required or implied: “On my honor, I have neither given nor received unauthorized aid in doing this assignment.” [The Honor Code](#) specifies a number of behaviors that are in violation of this code and the possible sanctions. Furthermore, you are obligated to report any condition that facilitates academic misconduct to appropriate personnel. If you have any questions or concerns, please consult with the instructor or TAs in this class.

Software Use

All faculty, staff, and students of the University are required and expected to obey the laws and legal agreements governing software use. Failure to do so can lead to monetary damages and/or criminal penalties for the individual violator. Because such violations are also against University policies and rules, disciplinary action will be taken as appropriate. We, the members of the University of Florida community, pledge to uphold ourselves and our peers to the highest standards of honesty and integrity.

Student Privacy

There are federal laws protecting your privacy with regards to grades earned in courses and on individual assignments. For more information, please see the [Notification to Students of FERPA Rights](#).

Campus Resources:

Health and Wellness

U Matter, We Care:

If you or a friend is in distress, please contact umatter@ufl.edu or 352 392-1575 so that a team member can reach out to the student.

Counseling and Wellness Center: counseling.ufl.edu/cwc, and 392-1575; and the University Police Department: 392-1111 or 9-1-1 for emergencies.

Sexual Assault Recovery Services (SARS)

Student Health Care Center, 392-1161.

University Police Department at 392-1111 (or 9-1-1 for emergencies), or police.ufl.edu.

Academic Resources

E-learning technical support, 352-392-4357 (select option 2) or e-mail to Learning-support@ufl.edu.

<https://lss.at.ufl.edu/help.shtml>.

Career Resource Center, Reitz Union, 392-1601. Career assistance and counseling.

<https://www.crc.ufl.edu/>.

Library Support, Various ways to receive assistance with respect to using the libraries or finding resources. <http://cms.uflib.ufl.edu/ask>.

Teaching Center, Broward Hall, 392-2010 or 392-6420. General study skills and tutoring. <https://teachingcenter.ufl.edu/>.

Writing Studio, 302 Tigert Hall, 846-1138. Help brainstorming, formatting, and writing papers. <https://writing.ufl.edu/writing-studio/>.

Student Complaints Campus <https://care.dso.ufl.edu>

On-Line Students Complaints